Accepted Manuscript

Characterization of Cu2SnS3 thin films prepared by sulfurization of co-evaporated Cu–SnS precursor layers

Yongshin Kim, In-Hwan Choi, Soon Yong Park

PII: S0040-6090(18)30634-5

DOI: doi:10.1016/j.tsf.2018.09.035

Reference: TSF 36897

To appear in: Thin Solid Films

Received date: 11 May 2018

Revised date: 14 September 2018 Accepted date: 14 September 2018

Please cite this article as: Yongshin Kim, In-Hwan Choi, Soon Yong Park, Characterization of Cu2SnS3 thin films prepared by sulfurization of co-evaporated Cu–SnS precursor layers. Tsf (2018), doi:10.1016/j.tsf.2018.09.035

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.



ACCEPTED MANUSCRIPT

Characterization of Cu₂SnS₃ thin films prepared by sulfurization of

co-evaporated Cu-SnS precursor layers

Yongshin Kim, In-Hwan Choi*, Soon Yong Park

The Department of Physics, Chung-ang University, 84 Heukseok-ro, Dongjak-gu, Seoul, 156-756

Republic of Korea.

*Corresponding Author, Email: ihchoi@cau.ac.kr, Phone: +82-2-820-5193, Fax: +82-2-825-4988

ABSTRACT

Monoclinic Cu₂SnS₃ thin films were prepared by sulfurizing Cu-SnS precursor layers

deposited by a co-evaporation method on soda-lime glass substrates. The morphological, optical

and electrical properties of the Cu₂SnS₃ thin films were investigated by scanning electron

microscopy, spectral transmittance, and Hall effect measurements. All Cu₂SnS₃ thin films prepared

in this study exhibited p-type conductivity and a direct band gap of 0.86-0.87 eV with a high

absorption coefficient (α >10⁴ cm⁻¹). However, carrier concentrations and electrical resistivities

varied noticeably, depending on their metallic composition ratios and sulfurization temperatures.

The thin film with a metallic composition ratio [Cu]/[Sn]=1.66 had a carrier concentration,

resistivity, and mobility of 3.12×10^{17} cm⁻³, 6.37 Ω ·cm, and 3.14 cm²/V·s, respectively. The

temperature dependence of electrical resistivity, carrier concentration, and Hall mobility of this thin

film was also obtained from liquid nitrogen temperature to room temperature to examine charge

transport properties.

Keywords: Copper tin sulfide; Hall effect, Optical absorption, Raman spectroscopy

Download English Version:

https://daneshyari.com/en/article/10156115

Download Persian Version:

 $\underline{https://daneshyari.com/article/10156115}$

Daneshyari.com